

ABSTRACT OF THE DISCLOSURE

The apparatus for forming a thin film includes a reaction chamber having a top portion, a sidewall portion and a bottom portion; a gas injector penetrating the top portion and letting a source element pass therethrough; a distributor connected to the gas injector, wherein a plurality of injection holes are formed in the distributor and the source element is injected through the plurality of injection holes; and a substrate heating member positioned in a reaction space defined by the top, bottom and sidewall portions of the reaction chamber, and arranged below the distributor.